In the Abstract:

Amend the Abstract as follows:

~~A computer architecture~~ Architecture and method ~~for transferring~~ to transfer data in ~~the generating and displaying~~ generation, display or printing [[of]] high edge placement accuracy images ~~having high edge placement accuracy derived~~ from ~~multiply~~ multiple exposures of [[a]] plurality of predefined patterns ~~, each having inherently~~ with lower edge placement accuracy. ~~The edge placement accuracy achieved can far exceed that normally afforded by the pixel size of the image transducer on which is formed the coarse pattern. The procedure starts with~~ A pattern is laid out on a grid finer ~~than,~~ or different from ~~,~~ the grid size ~~defined by the~~ of image transducer pixel size ~~of the image transducer, which is~~ overlaid by [[the]] transducer grid and converted to n ~~different~~ patterns compatible with [[the]] transducer grid. When ~~suitably~~ combined by partial exposures ~~that weight the~~ weighting patterns unevenly, the n patterns generate a ~~viewable or recordable~~ an image with line edge positions ~~that are~~ a fraction $(1/(2^n-1))$ of [[the]] transducer grid size. For most picture display ~~applications~~ and ~~for a~~ step-and-repeat lithography ~~application~~ applications, [[the]] pattern stored in [[the]] first memory is displayed or partially exposed once, and [[the]] remaining patterns ~~stored in memory~~ are displayed or partially exposed 2^{m-1} times ~~where~~ m ~~is the~~ being copy number ~~of the copy~~ of the pattern. ~~By superimposing~~ Superimposing 2^n-1 exposures in ~~the time it takes the~~ human eye to scene integration time ~~integrate a scene~~, [[a]] picture with improved line placement accuracy is perceived. ~~Similarly, superimposing 2^n-1 partial exposures in photosensitive recording medium will produce an improved recorded image. The present invention is particularly applicable to applications involving the transfer of large amounts of data in a short time interval, such as maskless step-and-repeat and maskless step-and-flash lithography.~~